Christopher K Ober

List of Publications by Year in Descending Order

512 papers	25,996 citations	76 h-index	147 g-index
593 ext. papers	27,632 ext. citations	6.7 avg, IF	6.84 L-index

#	Paper	IF	Citations
512	New Approaches to EUV Photoresists: Studies of Polyacetals and Polypeptoids to Expand the Photopolymer Toolbox. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2021**, 34, 71-74	0.7	3
511	Polymer-Grafted Nanoparticles (PGNs) with Adjustable Graft-Density and Interparticle Hydrogen Bonding Interaction. *Macromolecular Rapid Communications*, **2021**, e2100629	4.8	1
510	High-Resolution Nanopatterning of Free-Standing, Self-Supported Helical Polypeptide Rod Brushes via Electron Beam Lithography.. *ACS Macro Letters*, **2021**, 10, 755-759	6.6	0
509	Amphiphilic Nitroxide-Bearing Siloxane-Based Block Copolymer Coatings for Enhanced Marine Fouling Release. *ACS Applied Materials & Interfaces*, **2021**, 13, 28790-28801	9.5	2
508	Using Liquid Crystals to Probe the Organization of Helical Polypeptide Brushes Induced by Solvent Pretreatment. *Macromolecules*, **2021**, 54, 7786-7795	5.5	1
507	Materials systems for 2-photon lithography **2020**, 143-174		1
506	Thermal Stability of π-Conjugated n-Ethylene-Glycol-Terminated Quaterthiophene Oligomers: A Computational and Experimental Study. *ACS Macro Letters*, **2020**, 9, 295-300	6.6	2
505	Terminology of polymers in advanced lithography (IUPAC Recommendations 2020). *Pure and Applied Chemistry*, **2020**, 92, 1861-1891	2.1	0
504	Silica-PMMA hairy nanoparticles prepared via phase transfer-assisted aqueous miniemulsion atom transfer radical polymerization. *Journal of Polymer Science*, **2020**, 58, 2310-2316	2.4	2
503	Quantifying internal charge transfer and mixed ion-electron transfer in conjugated radical polymers. *Chemical Science*, **2020**, 11, 9962-9970	9.4	7
502	Three-Dimensional Printing of Hierarchical Porous Architectures. *Chemistry of Materials*, **2019**, 31, 10017–10022	9.6	11
501	Aqueous one-pot synthesis of epoxy-functional diblock copolymer worms from a single monomer: new anisotropic scaffolds for potential charge storage applications. *Polymer Chemistry*, **2019**, 10, 194-200	4.9	26
500	The Role of Hydrogen Bonding in Peptoid-Based Marine Antifouling Coatings. *Macromolecules*, **2019**, 52, 1287-1295	5.5	30
499	Structure Control of a π-Conjugated Oligothiophene-Based Liquid Crystal for Enhanced Mixed Ion/Electron Transport Characteristics. *ACS Nano*, **2019**, 13, 7665-7675	16.7	17
498	Polymer-Based Marine Antifouling and Fouling Release Surfaces: Strategies for Synthesis and Modification. *Annual Review of Chemical and Biomolecular Engineering*, **2019**, 10, 241-264	8.9	59
497	Polymer Brushes: Polymer Brushes on Hexagonal Boron Nitride (Small 19/2019). *Small*, **2019**, 15, 1970099	11	1
496	Entropic death of nonpatterned and nanopatterned polyelectrolyte brushes. *Journal of Polymer Science Part A*, **2019**, 57, 1283-1295	2.5	5

495	Spatially Controlled Transience of Graphene-Polymer Electronics with Silicon Singulation. *Advanced Functional Materials*, **2019**, 29, 1900592	15.6	1
494	Polymer Brushes on Hexagonal Boron Nitride. *Small*, **2019**, 15, e1805228	11	12
493	Block copolymers containing stable radical and fluorinated blocks with long-range ordered morphologies prepared by anionic polymerization. *Polymer Chemistry*, **2019**, 10, 5094-5102	4.9	7
492	Chemical reaction and diffusion kinetics during laser-induced submillisecond heating for lithographic applications. *Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics*, **2019**, 37, 041601	1.3	0
491	Radical sensitive Zinc-based nanoparticle EUV photoresists **2019**,		1
490	Metal Organic Cluster Photoresists for EUV Lithography. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2019**, 32, 711-714	0.7	1
489	Stability and microbial toxicity of HfO2 and ZrO2 nanoparticles for photolithography. *Green Materials*, **2019**, 7, 109-117	3.2	0
488	Self-Assembly Behavior of an Oligothiophene-Based Conjugated Liquid Crystal and Its Implication for Ionic Conductivity Characteristics. *Advanced Functional Materials*, **2019**, 29, 1805220	15.6	15
487	Flexible Hydrophobic Antifouling Coating with Oriented Nanotopography and Nonleaking Capsaicin. *ACS Applied Materials & Interfaces*, **2018**, 10, 9718-9726	9.5	32
486	Mini Monomer Encapsulated Emulsion Polymerization of PMMA Using Aqueous ARGET ATRP. *ACS Macro Letters*, **2018**, 7, 459-463	6.6	17
485	In pursuit of Moore's Law: polymer chemistry in action. *Polymer Journal*, **2018**, 50, 45-55	2.7	10
484	Biologically Complex Planar Cell Plasma Membranes Supported on Polyelectrolyte Cushions Enhance Transmembrane Protein Mobility and Retain Native Orientation. *Langmuir*, **2018**, 34, 1061-1072	4	25
483	Charge Transport in Conjugated Polymers with Pendent Stable Radical Groups. *Chemistry of Materials*, **2018**, 30, 4799-4807	9.6	21
482	Electroluminescence from Solution-Processed Pinhole-Free Nanometer-Thickness Layers of Conjugated Polymers. *Nano Letters*, **2018**, 18, 5382-5388	11.5	2
481	UV-Triggered Transient Electrospun Poly(propylene carbonate)/Poly(phthalaldehyde) Polymer Blend Fiber Mats. *ACS Applied Materials & Interfaces*, **2018**, 10, 28928-28935	9.5	4
480	Engineered nanomaterials and human health: Part 1. Preparation, functionalization and characterization (IUPAC Technical Report). *Pure and Applied Chemistry*, **2018**, 90, 1283-1324	2.1	27
479	Engineered nanomaterials and human health: Part 2. Applications and nanotoxicology (IUPAC Technical Report). *Pure and Applied Chemistry*, **2018**, 90, 1325-1356	2.1	17
478	Metal Organic Framework-Inspired Metal-Containing Clusters for High-Resolution Patterning. *Chemistry of Materials*, **2018**, 30, 4124-4133	9.6	29

477	EUV photolithography: resist progress in metal organic complex photoresists. *Journal of Micro/Nanolithography, MEMS, and MOEMS*, **2018**, 18, 1	0.7	11
476	Patterning mechanism of metal based hybrid EUV resists **2018**,		1
475	EUV photolithography: resist progress and challenges **2018**,		4
474	EUV metal oxide hybrid photoresists: ultra-small structures for high-resolution patterning **2018**,		1
473	Impact of the Synthesis Method on the Solid-State Charge Transport of Radical Polymers. *Journal of Materials Chemistry C*, **2018**, 6, 111-118	7.1	33
472	Facile Preparation of Epoxide-Functionalized Surfaces via Photocurable Copolymer Coatings and Subsequent Immobilization of Iminodiacetic Acids. *ACS Applied Materials & Interfaces*, **2018**, 10, 40871-40879	9.5	13
471	Progress in metal organic cluster EUV photoresists. *Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics*, **2018**, 36, 06J504	1.3	3
470	Materials Overview for 2-Photon 3D Printing Applications. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2018**, 31, 425-429	0.7	2
469	The Challenges of Highly Sensitive EUV Photoresists. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2018**, 31, 261-265	0.7	5
468	Synthesis, Processing, and Characterization of Helical Polypeptide Rod Coil Mixed Brushes. *ACS Macro Letters*, **2018**, 7, 1186-1191	6.6	7
467	Fifty years of the Baier curve: progress in understanding antifouling coatings. *Green Materials*, **2017**, 5, 1-3	3.2	13
466	Model Amphiphilic Block Copolymers with Tailored Molecular Weight and Composition in PDMS-Based Films to Limit Soft Biofouling. *ACS Applied Materials & Interfaces*, **2017**, 9, 16505-16516	9.5	24
465	50th Anniversary Perspective: Polymer Brushes: Novel Surfaces for Future Materials. *Macromolecules*, **2017**, 50, 4089-4113	5.5	265
464	Transient Fiber Mats of Electrospun Poly(Propylene Carbonate) Composites with Remarkable Mechanical Strength. *ACS Applied Materials & Interfaces*, **2017**, 9, 25495-25505	9.5	10
463	Morphology of Nanostructured Polymer Brushes Dependent on Production and Treatment. *Macromolecules*, **2017**, 50, 4715-4724	5.5	6
462	Ultrafast Self-Assembly of Sub-10 nm Block Copolymer Nanostructures by Solvent-Free High-Temperature Laser Annealing. *ACS Applied Materials & Interfaces*, **2017**, 9, 31317-31324	9.5	29
461	Role of Backbone Chemistry and Monomer Sequence in Amphiphilic Oligopeptide- and Oligopeptoid-Functionalized PDMS- and PEO-Based Block Copolymers for Marine Antifouling and Fouling Release Coatings. *Macromolecules*, **2017**, 50, 2656-2667	5.5	44
460	Directed self-assembly: A dress code for block copolymers. *Nature Nanotechnology*, **2017**, 12, 507-508	28.7	6

459	Nanoparticle photoresist studies for EUV lithography **2017**,		12
458	Perpendicular Orientation Control without Interfacial Treatment of RAFT-Synthesized High-Block Copolymer Thin Films with Sub-10 nm Features Prepared via Thermal Annealing. *ACS Applied Materials & Interfaces*, **2017**, 9, 31266-31278	9.5	47
457	Reduced Lateral Confinement and Its Effect on Stability in Patterned Strong Polyelectrolyte Brushes. *Langmuir*, **2017**, 33, 3296-3303	4	10
456	Oligopeptide-modified hydrophobic and hydrophilic polymers as antifouling coatings. *Green Materials*, **2017**, 5, 31-43	3.2	6
455	Recent Progress in EUV Metal Oxide Photoresists. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2017**, 30, 93-97	0.7	4
454	Manipulation of cell adhesion and dynamics using RGD functionalized polymers. *Journal of Materials Chemistry B*, **2017**, 5, 6307-6316	7.3	26
453	Correction: Manipulation of cell adhesion and dynamics using RGD functionalized polymers. *Journal of Materials Chemistry B*, **2017**, 5, 6973	7.3	1
452	Lithography performance and environmental compatibility of PFOS-free photoacid generators. *Green Materials*, **2017**, 5, 173-181	3.2	2
451	MEMS analogous micro-patterning of thermotropic nematic liquid crystalline elastomer films using a fluorinated photoresist and a hard mask process. *Journal of Materials Chemistry C*, **2017**, 5, 12635-12644	7.1	13
450	Extreme ultraviolet resist materials for sub-7 nm patterning. *Chemical Society Reviews*, **2017**, 46, 4855-4866	39.5	124
449	Elucidating the patterning mechanism of zirconium-based hybrid photoresists. *Journal of Micro/Nanolithography, MEMS, and MOEMS*, **2017**, 16, 1	0.7	12
448	Kinetics of Block Copolymer Phase Segregation during Sub-millisecond Transient Thermal Annealing. *Macromolecules*, **2016**, 49, 6462-6470	5.5	19
447	Effects of surface-active block copolymers with oxyethylene and fluoroalkyl side chains on the antifouling performance of silicone-based films. *Biofouling*, **2016**, 32, 81-93	3.3	37
446	Interface manipulated two-phase nanostructure in a triblock terpolymer with a short middle segment. *Polymer Journal*, **2016**, 48, 533-538	2.7	3
445	Transient micropackets for silicon dioxide and polymer-based vaporizable electronics **2016**,		3
444	Solubility studies of inorganic-organic hybrid nanoparticle photoresists with different surface functional groups. *Nanoscale*, **2016**, 8, 1338-43	7.7	35
443	Source-based nomenclature for single-strand homopolymers and copolymers (IUPAC Recommendations 2016). *Pure and Applied Chemistry*, **2016**, 88, 1073-1100	2.1	10
442	The development of fluorous photolithographic materials and their applications to achieve flexible organic electronic devices. *Flexible and Printed Electronics*, **2016**, 1, 023001	3.1	12

441	Ambiguous anti-fouling surfaces: Facile synthesis by light-mediated radical polymerization. *Journal of Polymer Science Part A*, **2016**, 54, 253-262	2.5	44
440	Positive Tone Nanoparticle Photoresists: New Insight on the Patterning Mechanism. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2016**, 29, 509-512	0.7	6
439	Precise Synthesis of Fluorine-containing Block Copolymers via RAFT. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2016**, 29, 705-708	0.7	6
438	Micrometer-Scale Ordering of Silicon-Containing Block Copolymer Thin Films via High-Temperature Thermal Treatments. *ACS Applied Materials & Interfaces*, **2016**, 8, 9897-908	9.5	16
437	Recent progress in nanoparticle photoresists development for EUV lithography **2016**,		7
436	Positive tone oxide nanoparticle EUV (ONE) photoresists **2016**,		4
435	Transient materials from thermally-sensitive polycarbonates and polycarbonate nanocomposites. *Polymer*, **2016**, 101, 59-66	3.9	13
434	Nanopatterning of Stable Radical Containing Block Copolymers for Highly Ordered Functional Nanomeshes. *Macromolecules*, **2016**, 49, 5884-5892	5.5	11
433	Nomenclature and graphic representations for chemically modified polymers (IUPAC Recommendations 2014). *Pure and Applied Chemistry*, **2015**, 87, 307-319	2.1	3
432	Zinc induced polyelectrolyte coacervate bioadhesive and its transition to a self-healing hydrogel. *RSC Advances*, **2015**, 5, 66871-66878	3.7	62
431	Studying the Mechanism of Hybrid Nanoparticle Photoresists: Effect of Particle Size on Photopatterning. *Chemistry of Materials*, **2015**, 27, 5027-5031	9.6	51
430	Systematic study of ligand structures of metal oxide EUV nanoparticle photoresists **2015**,		1
429	New developments in ligand-stabilized metal oxide nanoparticle photoresists for EUV lithography **2015**,		1
428	Design, Synthesis, and Use of Y-Shaped ATRP/NMP Surface Tethered Initiator. *ACS Macro Letters*, **2015**, 4, 606-610	6.6	14
427	Widely Tunable Morphologies in Block Copolymer Thin Films Through Solvent Vapor Annealing Using Mixtures of Selective Solvents. *Advanced Functional Materials*, **2015**, 25, 3057-3065	15.6	70
426	Photopatterning of Indomethacin Thin Films: a Solvent-Free Vapor-Deposited Photoresist. *ACS Applied Materials & Interfaces*, **2015**, 7, 23398-401	9.5	2
425	Block Copolymers as Antifouling and Fouling Resistant Coatings **2015**, 881-924		1
424	Understanding of PS-b-PMMA phase segregation under laser-induced millisecond thermal annealing **2015**,		4

423	Control of polystyrene-block-poly(methyl methacrylate) directed self-assembly by laser-induced millisecond thermal annealing. *Journal of Micro/ Nanolithography, MEMS, and MOEMS*, **2015**, 14, 031205	0.7	9
422	Supercritical CO2-philic nanoparticles suitable for determining the viability of carbon sequestration in shale. *Environmental Science: Nano*, **2015**, 2, 288-296	7.1	4
421	A glucose sensor via stable immobilization of the GOx enzyme on an organic transistor using a polymer brush. *Journal of Polymer Science Part A*, **2015**, 53, 372-377	2.5	50
420	Block copolymers with stable radical and fluorinated groups by ATRP. *MRS Communications*, **2015**, 5, 441-446	2.7	6
419	Laser Spike Annealing of DSA Photoresists. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2015**, 28, 631-634	0.7	8
418	Oxide Nanoparticle EUV (ONE) Photoresists: Current Understanding of the Unusual Patterning Mechanism. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2015**, 28, 515-518	0.7	15
417	Vertical Oriented Lamellar Formation of Fluorine- and Silicon-containing Block Copolymers without Neutral Layers. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2015**, 28, 649-652	0.7	9
416	Amphiphilic oligopeptides grafted to PDMS-based diblock copolymers for use in antifouling and fouling release coatings. *Polymers for Advanced Technologies*, **2015**, 26, 829-836	3.2	23
415	Alkali Metal Based Micro Combustion Using Graphene Micro-valve Trigger. *Journal of Physics: Conference Series*, **2015**, 660, 012033	0.3	2
414	Amphiphilic triblock copolymers with PEGylated hydrocarbon structures as environmentally friendly marine antifouling and fouling-release coatings. *Biofouling*, **2014**, 30, 589-604	3.3	57
413	Thermally induced orientational flipping of cylindrical phase diblock copolymers. *Journal of Materials Chemistry C*, **2014**, 2, 2175-2182	7.1	18
412	Controlled roughness reduction of patterned resist polymers using laser-induced sub-millisecond heating. *Journal of Materials Chemistry C*, **2014**, 2, 9115-9121	7.1	4
411	Phase behaviour of PMMA-b-PHEMA with solvents methanol and THF: modelling and comparison to the experiment. *Soft Matter*, **2014**, 10, 6172-81	3.6	4
410	Generalized platform for antibody detection using the antibody catalyzed water oxidation pathway. *Journal of the American Chemical Society*, **2014**, 136, 1879-83	16.4	27
409	Photolithographic Patterning of Organic Electronic Materials **2014**, 399-420		
408	C60-containing polymers for electron beam lithography. *Polymer Bulletin*, **2014**, 71, 2395-2405	2.4	6
407	Control of biofouling on reverse osmosis polyamide membranes modified with biocidal nanoparticles and antifouling polymer brushes. *Journal of Materials Chemistry B*, **2014**, 2, 1724-1732	7.3	135
406	Laser-induced sub-millisecond heating reveals distinct tertiary ester cleavage reaction pathways in a photolithographic resist polymer. *ACS Nano*, **2014**, 8, 5746-56	16.7	22

405	Metal Oxide Nanoparticle Photoresists for EUV Patterning. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2014**, 27, 663-666	0.7	33
404	Line width roughness reduction by rational design of photoacid generator for sub-millisecond laser post-exposure bake **2014**,		2
403	Increasing sensitivity of oxide nanoparticle photoresists **2014**,		9
402	Control of PS-b-PMMA directed self-assembly registration by laser induced millisecond thermal annealing **2014**,		11
401	Nanopatterning with tailored molecules **2014**,		2
400	The solvent problem: Redissolution of macromolecules in solution-processed organic electronics. *Macromolecular Research*, **2013**, 21, 248-256	1.9	16
399	Biodegradability, cytotoxicity, and physicochemical treatability of two novel perfluorooctane sulfonate-free photoacid generators. *Archives of Environmental Contamination and Toxicology*, **2013**, 64, 187-97	3.2	5
398	Inkjet printing of fluorinated materials and their application to patterning organic semiconductors. *Journal of Materials Chemistry C*, **2013**, 1, 5647	7.1	8
397	Responsive and patterned polymer brushes. *Journal of Polymer Science, Part B: Polymer Physics*, **2013**, 51, 1457-1472	2.6	46
396	A brief guide to polymer nomenclature from IUPAC. *Colloid and Polymer Science*, **2013**, 291, 457-458	2.4	2
395	A Brief Guide to Polymer Nomenclature. *Polymer Degradation and Stability*, **2013**, 98, 1-2	4.7	4
394	Early detection of Candida albicans biofilms at porous electrodes. *Analytical Biochemistry*, **2013**, 433, 192-201	3.1	12
393	Fibronectin conformation regulates the proangiogenic capability of tumor-associated adipogenic stromal cells. *Biochimica Et Biophysica Acta - General Subjects*, **2013**, 1830, 4314-20	4	32
392	ConfChem Conference on A Virtual Colloquium to Sustain and Celebrate IYC 2011 Initiatives in Global Chemical Education The Continuing Celebration of IYC 2011: What the IUPAC Polymer Division Is Doing To Keep Things Going. *Journal of Chemical Education*, **2013**, 90, 1559-1560	2.4	1
391	Improved antifouling properties of polymer membranes using a 'layer-by-layer' mediated method. *Journal of Materials Chemistry B*, **2013**, 1, 5651-5658	7.3	33
390	From surface coatings to polymer nanofilms: lifting off polymer brushes. *RSC Advances*, **2013**, 3, 18482	3.7	4
389	A Brief Guide to Polymer Nomenclature. *Polymer*, **2013**, 54, 3-4	3.9	5
388	A Brief Guide to Polymer Nomenclature. *Polymer International*, **2013**, 62, I-II	3.3	1

387	Photo-cleavable anti-fouling polymer brushes: A simple and versatile platform for multicomponent protein patterning. *Polymer*, **2013**, 54, 1762-1767	3.9	14
386	A brief guide to polymer nomenclature. *Reactive and Functional Polymers*, **2013**, 73, iv-v	4.6	1
385	Characterization of Polymer Brush Membranes via HF Etch Liftoff Technique.. *ACS Macro Letters*, **2013**, 2, 241-245	6.6	16
384	Orthogonal patterning of multiple biomolecules using an organic fluorinated resist and imprint lithography. *Biomacromolecules*, **2013**, 14, 993-1002	6.9	16
383	Semi-perfluoroalkyl polyfluorene with varying fluorine content: synthesis and photophysical properties. *Polymer Chemistry*, **2013**, 4, 5291	4.9	8
382	Biomimetic polymer brushes containing tethered acetylcholine analogs for protein and hippocampal neuronal cell patterning. *Biomacromolecules*, **2013**, 14, 529-37	6.9	39
381	Oxide nanoparticle EUV resists: toward understanding the mechanism of positive and negative tone patterning **2013**,		16
380	Line edge roughness of high deprotection activation energy photoresist by using sub-millisecond post exposure bake **2013**,		4
379	Non-aqueous negative-tone development of inorganic metal oxide nanoparticle photoresists for next generation lithography **2013**,		4
378	Nanoparticle Photoresists: Ligand Exchange as a New, Sensitive EUV Patterning Mechanism. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2013**, 26, 659-664	0.7	30
377	Combinatorial techniques to efficiently investigate and optimize organic thin film processing and properties. *Molecules*, **2013**, 18, 4120-39	4.8	4
376	Polymer Brushes as Functional, Patterned Surfaces for Nanobiotechnology. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2013**, 25, 53-56	0.7	8
375	The role of hydrogels with tethered acetylcholine functionality on the adhesion and viability of hippocampal neurons and glial cells. *Biomaterials*, **2012**, 33, 2473-81	15.6	27
374	Amphiphilic block copolymer surface composition: Effects of spin coating versus spray coating. *Polymer*, **2012**, 53, 1321-1327	3.9	13
373	Terminology for aggregation and self-assembly in polymer science (IUPAC Recommendations 2013). *Pure and Applied Chemistry*, **2012**, 85, 463-492	2.1	17
372	Reconstruction of surfaces from mixed hydrocarbon and PEG components in water: responsive surfaces aid fouling release. *Biomacromolecules*, **2012**, 13, 1864-74	6.9	37
371	Neutron reflectivity characterization of the photoacid reaction-diffusion latent and developed images of molecular resists for extreme ultraviolet lithography. *Langmuir*, **2012**, 28, 7665-78	4	12
370	Dual Mode Patterning of Fluorine-Containing Block Copolymers through Combined Top-down and Bottom-up Lithography. *Chemistry of Materials*, **2012**, 24, 1454-1461	9.6	31

369	Tailored star block copolymer architecture for high performance chemically amplified resists. *Advanced Materials*, **2012**, 24, 5939-44	24	10
368	Preparation and characterization of amphiphilic triblock terpolymer-based nanofibers as antifouling biomaterials. *Biomacromolecules*, **2012**, 13, 1606-14	6.9	24
367	Kinetic rates of thermal transformations and diffusion in polymer systems measured during sub-millisecond laser-induced heating. *ACS Nano*, **2012**, 6, 5830-6	16.7	25
366	Organic field-effect transistors and solar cells using novel high electron-affinity conjugated copolymers based on alkylbenzotriazole and benzothiadiazole. *Journal of Materials Chemistry*, **2012** , 22, 4436		26
365	Environmentally friendly patterning of thin films in linear methyl siloxanes. *Journal of Materials Chemistry*, **2012**, 22, 5746		9
364	Tailored star-shaped statistical teroligomers viaATRP for lithographic applications. *Journal of Materials Chemistry*, **2012**, 22, 73-79		12
363	Multicomponent Physical Vapor Deposited Films with Homogeneous Molecular Material Distribution Featuring Improved Resist Sensitivity. *Advanced Functional Materials*, **2012**, 22, 3865-3873	15.6	4
362	Electrical control of protein conformation. *Advanced Materials*, **2012**, 24, 2501-5	24	62
361	Tightly bound ligands for hafnium nanoparticle EUV resists **2012**,		2
360	A brief guide to polymer nomenclature (IUPAC Technical Report). *Pure and Applied Chemistry*, **2012**, 84, 2167-2169	2.1	30
359	A new inorganic EUV resist with high-etch resistance **2012**,		24
358	Synthesis and characterization of high-throughput nanofabricated poly(4-hydroxy styrene) membranes for in vitro models of barrier tissue. *Tissue Engineering - Part C: Methods*, **2012**, 18, 667-76	2.9	10
357	Deprotection reaction kinetics in chemically amplified photoresists determined by sub-millisecond post exposure bake **2012**,		1
356	Investigation of acid diffusion during laser spike annealing with systematically designed photoacid generators **2012**,		4
355	Nanoparticle photoresists from HfO2 and ZrO2 for EUV patterning. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2012**, 25, 583-586	0.7	37
354	Top-down Meets Bottom up: Block Copolymers with Photoreactive Segments. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2012**, 25, 17-20	0.7	3
353	New poly(dimethylsiloxane)/poly(perfluorooctylethyl acrylate) block copolymers: structure and order across multiple length scales in thin films. *Journal of Materials Chemistry*, **2011**, 21, 15357		32
352	Block Copolymer Nanostructured Thin Films for Advanced Patterning **2011**, 763-790		2

351	A general approach to controlling the surface composition of poly(ethylene oxide)-based block copolymers for antifouling coatings. *Langmuir*, **2011**, 27, 13762-72	4	102
350	High-performance electron-transporting polymers derived from a heteroaryl bis(trifluoroborate). *Journal of the American Chemical Society*, **2011**, 133, 9949-51	16.4	72
349	Characterization of the Non-uniform Reaction in Chemically Amplified Calix[4]resorcinarene Molecular Resist Thin Films. *Australian Journal of Chemistry*, **2011**, 64, 1065	1.2	4
348	Patterning by Photolithography **2011**, 475-499		2
347	Polymer brushes for electrochemical biosensors. *Soft Matter*, **2011**, 7, 297-302	3.6	55
346	Orthogonal processing: A new strategy for organic electronics. *Chemical Science*, **2011**, 2, 1178	9.4	92
345	Photoinduced ordering of block copolymers. *Nano Letters*, **2011**, 11, 1153-60	11.5	20
344	Applications of Controlled Macromolecular Architectures to Lithography **2011**, 2295-2330		1
343	Time Dependent Behavior of Chemically Amplified Resist Characterized under Sub-millisecond Post Exposure Bake. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2011**, 24, 487-490	0.7	6
342	Studies of Environmentally Friendly Solvent-based Developers. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2011**, 24, 239-240	0.7	1
341	Fouling-resistant polymer brush coatings. *Polymer*, **2011**, 52, 5419-5425	3.9	39
340	Fluorine-free mixed amphiphilic polymers based on PDMS and PEG side chains for fouling release applications. *Biofouling*, **2011**, 27, 589-602	3.3	80
339	Synthesis, molecular, and morphological characterization of initial and modified diblock copolymers with organic acid chloride derivatives. *Journal of Polymer Science Part A*, **2011**, 49, 4292-4305	2.5	15
338	Orthogonal processing and patterning enabled by highly fluorinated light-emitting polymers. *Advanced Materials*, **2011**, 23, 735-9	24	35
337	Detection of transmitter release from single living cells using conducting polymer microelectrodes. *Advanced Materials*, **2011**, 23, H184-8	24	67
336	Combinatorial optimization of a molecular glass photoresist system for electron beam lithography. *Advanced Materials*, **2011**, 23, 5404-8	24	14
335	Photo-switchable polyelectrolyte brush for dual protein patterning. *Journal of Materials Chemistry*, **2011**, 21, 13789		12
334	Properties of PVA/HfO2 Hybrid Electrospun Fibers and Calcined Inorganic HfO2 Fibers. *Journal of Physical Chemistry C*, **2011**, 115, 5535-5544	3.8	18

333	Robert W. Lenz. *Macromolecules*, **2011**, 44, 1731-1731	5.5	
332	Triblock Copolymers with Grafted Fluorine-Free, Amphiphilic, Non-Ionic Side Chains for Antifouling and Fouling-Release Applications. *Macromolecules*, **2011**, 44, 4783-4792	5.5	89
331	Cellular responses to patterned poly(acrylic acid) brushes. *Langmuir*, **2011**, 27, 7016-23	4	40
330	Fluorinated amphiphilic polymers and their blends for fouling-release applications: the benefits of a triblock copolymer surface. *ACS Applied Materials & Interfaces*, **2011**, 3, 3366-74	9.5	95
329	Probing electric field response of LC thermosets via time-resolved X-ray and dielectric spectroscopy. *Polymer*, **2011**, 52, 2206-2213	3.9	5
328	LWR reduction and flow of chemically amplified resist patterns during sub-millisecond heating **2011**,		10
327	Addressing challenges in lithography using sub-millisecond post exposure bake of chemically amplified resists **2011**,		4
326	Fabrication of polymer-based electronic circuits using photolithography. *Applied Physics Letters*, **2011**, 99, 183308	3.4	17
325	Development of an inorganic nanoparticle photoresist for EUV, e-beam, and 193nm lithography **2011**,		25
324	Emerging applications of stimuli-responsive polymer materials. *Nature Materials*, **2010**, 9, 101-13	27	4474
323	New self-assembly strategies for next generation lithography **2010**,		1
322	Development of an inorganic photoresist for DUV, EUV, and electron beam imaging **2010**,		26
321	All-dry processible and PAG-attached molecular glasses for improved lithographic performance **2010**,		1
320	An electrochemical glucose sensor from an organically modified nanocomposite of viologen and TiO2. *Journal of Nanoscience and Nanotechnology*, **2010**, 10, 6869-73	1.3	6
319	Comparison of star and linear ArF resists **2010**,		3
318	Sub-millisecond post exposure bake of chemically amplified resists by CO 2 laser heat treatment **2010**,		9
317	Role of solvent dielectric properties on charge transfer from PbS nanocrystals to molecules. *Nano Letters*, **2010**, 10, 318-23	11.5	73
316	Patterning of polymer brushes. A direct approach to complex, sub-surface structures. *Nano Letters*, **2010**, 10, 3873-9	11.5	44

315	Amphiphilic surface active triblock copolymers with mixed hydrophobic and hydrophilic side chains for tuned marine fouling-release properties. *Langmuir*, **2010**, 26, 9772-81	4	90
314	Semiperfluoroalkyl Polyfluorenes for Orthogonal Processing in Fluorous Solvents. *Macromolecules*, **2010**, 43, 1195-1198	5.5	36
313	Surface structures of an amphiphilic tri-block copolymer in air and in water probed using sum frequency generation vibrational spectroscopy. *Langmuir*, **2010**, 26, 11337-43	4	16
312	NEXAFS Depth Profiling of Surface Segregation in Block Copolymer Thin Films. *Macromolecules*, **2010**, 43, 4733-4743	5.5	43
311	Direct patterning of intrinsically electron beam sensitive polymer brushes. *ACS Nano*, **2010**, 4, 771-80	16.7	64
310	Characterization of the Photoacid Diffusion Length and Reaction Kinetics in EUV Photoresists with IR Spectroscopy. *Macromolecules*, **2010**, 43, 4275-4286	5.5	39
309	Direct synthesis of quaternized polymer brushes and their application for guiding neuronal growth. *Biomacromolecules*, **2010**, 11, 2027-32	6.9	24
308	High refractive index and high transparency HfO2 nanocomposites for next generation lithography. *Journal of Materials Chemistry*, **2010**, 20, 5186		50
307	Reversible Morphology Control in Block Copolymer Films via Solvent Vapor Processing: An In Situ GISAXS study. *Macromolecules*, **2010**, 43, 4253-4260	5.5	144
306	Orthogonal lithography for organic electronics **2010**,		5
305	Architectural Effects on Acid Reaction-Diffusion Kinetics in Molecular Glass Photoresists. *Chemistry of Materials*, **2010**, 22, 3093-3098	9.6	15
304	Antimicrobial behavior of semifluorinated-quaternized triblock copolymers against airborne and marine microorganisms. *ACS Applied Materials & Interfaces*, **2010**, 2, 703-11	9.5	45
303	A Glucose Sensor Based on an Organic Electrochemical Transistor Structure Using a Vapor Polymerized Poly(3,4-ethylenedioxythiophene) Layer. *Japanese Journal of Applied Physics*, **2010**, 49, 01AE10	1.4	19
302	Protein adsorption resistance of anti-biofouling block copolymers containing amphiphilic side chains. *Soft Matter*, **2010**, 6, 3237	3.6	76
301	Synthesis and Processing of Organic Materials in Supercritical Carbon Dioxide. *MRS Bulletin*, **2009**, 34, 108-115	3.2	7
300	Molecular glass resists developable in supercritical carbon dioxide for 193 nm lithography **2009**,		2
299	Submillisecond post-exposure bake of chemically amplified resists by CO2 laser spike annealing. *Journal of Vacuum Science & Technology B*, **2009**, 27, 3020		5
298	High-index nanocomposite photoresist for 193-nm lithography **2009**,		4

297	Orthogonal Patterning of PEDOT:PSS for Organic Electronics using Hydrofluoroether Solvents. *Advanced Materials*, **2009**, 21, 2314-2317	24	146
296	Fluorine- and siloxane-containing polymers for supercritical carbon dioxide lithography. *Polymer International*, **2009**, 58, 302-306	3.3	9
295	Quantitative measurement of the polydispersity in the extent of functionalization of glass-forming calix[4]resorcinarenes. *Rapid Communications in Mass Spectrometry*, **2009**, 23, 1957-62	2.2	2
294	Surface engineering of styrene/PEGylated-fluoroalkyl styrene block copolymer thin films. *Journal of Polymer Science Part A*, **2009**, 47, 267-284	2.5	52
293	ABC triblock surface active block copolymer with grafted ethoxylated fluoroalkyl amphiphilic side chains for marine antifouling/fouling-release applications. *Langmuir*, **2009**, 25, 12266-74	4	135
292	Selective area control of self-assembled pattern architecture using a lithographically patternable block copolymer. *ACS Nano*, **2009**, 3, 1761-6	16.7	54
291	Development of a directly patterned low-surface-energy polymer brush in supercritical carbon dioxide. *ACS Applied Materials & Interfaces*, **2009**, 1, 2013-20	9.5	10
290	Direct three-dimensional microfabrication of hydrogels via two-photon lithography in aqueous solution. *Chemistry of Materials*, **2009**, 21, 2003-2006	9.6	96
289	Sulfonium Salts of Alicyclic Group Functionalized Semifluorinated Alkyl Ether Sulfonates As Photoacid Generators. *Chemistry of Materials*, **2009**, 21, 4037-4046	9.6	11
288	Release of nerve growth factor from HEMA hydrogel-coated substrates and its effect on the differentiation of neural cells. *Biomacromolecules*, **2009**, 10, 174-83	6.9	103
287	Preventing nonspecific adsorption on polymer brush covered gold electrodes using a modified ATRP initiator. *Biomacromolecules*, **2009**, 10, 2750-8	6.9	34
286	Research in Macromolecular Science: Challenges and Opportunities for the Next Decade. *Macromolecules*, **2009**, 42, 465-471	5.5	139
285	Fluorinated Quaternary Ammonium Salts as Dissolution Aids for Polar Polymers in Environmentally Benign Supercritical Carbon Dioxide. *Chemistry of Materials*, **2009**, 21, 3125-3135	9.6	11
284	Solid state NMR investigation of photoresist molecular glasses including blend behavior with a photoacid generator. *Journal of Materials Chemistry*, **2009**, 19, 2683		14
283	Cross-linkable molecular glasses: low dielectric constant materials patternable in hydrofluoroethers. *ACS Applied Materials & Interfaces*, **2009**, 1, 2363-70	9.5	25
282	Acid-diffusion behaviour in organic thin films and its effect on patterning. *Journal of Materials Chemistry*, **2009**, 19, 2986		16
281	High voltage polymer solar cell patterned with photolithography. *Journal of Materials Chemistry*, **2009**, 19, 5394		13
280	Environmentally friendly patterning of molecular waterwheel (Noria) in supercritical carbon dioxide. *Journal of Materials Chemistry*, **2009**, 19, 4622		25

279	Non-ionic photo-acid generators for applications in two-photon lithography. *Journal of Materials Chemistry*, **2009**, 19, 505-513		34
278	Dissociation behavior of weak polyelectrolyte brushes on a planar surface. *Langmuir*, **2009**, 25, 4774-9	4	140
277	Orthogonal Processing: A Novel Photolithographic Patterning Method for Organic Electronics. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2009**, 22, 565-569	0.7	23
276	Molecular glass resists for next-generation lithography **2009**,		3
275	High refractive index nanoparticle fluids for 193-nm immersion lithography **2009**,		1
274	Settlement of Ulva zoospores on patterned fluorinated and PEGylated monolayer surfaces. *Langmuir*, **2008**, 24, 503-10	4	116
273	Hydroxyphenylbenzene derivatives as glass forming molecules for high resolution photoresists. *Journal of Materials Chemistry*, **2008**, 18, 1903		19
272	Towards environmentally friendly, dry deposited, water developable molecular glass photoresists. *Physical Chemistry Chemical Physics*, **2008**, 10, 1257-62	3.6	15
271	Dry photolithographic patterning process for organic electronic devices using supercritical carbon dioxide as a solvent. *Journal of Materials Chemistry*, **2008**, 18, 3087		39
270	A novel noria (water-wheel-like cyclic oligomer) derivative as a chemically amplified electron-beam resist material. *Journal of Materials Chemistry*, **2008**, 18, 3588		46
269	A Fundamental Study on Dissolution Behavior of High-Resolution Molecular Glass Photoresists. *Chemistry of Materials*, **2008**, 20, 7292-7300	9.6	21
268	Study of the Structure□Properties Relationship of Phenolic Molecular Glass Resists for Next Generation Photolithography. *Chemistry of Materials*, **2008**, 20, 1606-1613	9.6	36
267	Three-dimensionally-patterned submicrometer-scale hydrogel/air networks that offer a new platform for biomedical applications. *Nano Letters*, **2008**, 8, 1456-60	11.5	33
266	Simple Fabrication of Micropatterned Mesoporous Silica Films Using Photoacid Generators in Block Copolymers□ *Chemistry of Materials*, **2008**, 20, 604-606	9.6	19
265	Nonplanar Surface Organization of Monodendrons in Side-Chain Modified Liquid Crystalline Block Copolymers.. *Macromolecules*, **2008**, 41, 9940-9945	5.5	3
264	Acid-sensitive semiperfluoroalkyl resorcinarene: an imaging material for organic electronics. *Journal of the American Chemical Society*, **2008**, 130, 11564-5	16.4	62
263	Acid-Labile, Chain-Scission Polymer Systems Used as Positive-Tone Photoresists Developable in Supercritical CO2. *Chemistry of Materials*, **2008**, 20, 2932-2936	9.6	11
262	Control of self-assembly of lithographically patternable block copolymer films. *ACS Nano*, **2008**, 2, 1396-402	17	130

261	Molecular glass resists for next generation lithography **2008**,		5
260	Supercritical Carbon Dioxide Compatible Salts: Synthesis and Application to Next Generation Lithography. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2008**, 21, 393-396	0.7	2
259	The use of Nanocomposite Materials for High Refractive Index Immersion Lithography. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2008**, 21, 621-629	0.7	6
258	The effect of EUV molecular glass architecture on the bulk dispersion of a photo-acid generator **2008**,		2
257	Development of an operational high refractive index resist for 193nm immersion lithography **2008**,		3
256	A comparison of the reaction-diffusion kinetics between model-EUV polymer and molecular-glass photoresists **2008**,		6
255	Characterization of the latent image to developed image in model EUV photoresists **2008**,		2
254	Development and evaluation of 193nm immersion generation-three fluid candidates **2008**,		2
253	An Efficient Route to Mesoporous Silica Films with Perpendicular Nanochannels. *Advanced Materials*, **2008**, 20, 246-251	24	48
252	Calix[4]resorcinarene Derivatives as High-Resolution Resist Materials for Supercritical CO2 Processing. *Advanced Materials*, **2008**, 20, 1303-1309	24	12
251	Hydrofluoroethers as Orthogonal Solvents for the Chemical Processing of Organic Electronic Materials. *Advanced Materials*, **2008**, 20, 3481-3484	24	128
250	Advances in polymers for anti-biofouling surfaces. *Journal of Materials Chemistry*, **2008**, 18, 3405		680
249	Dissolution phenomena of phenolic molecular glass photoresist films in supercritical CO2. *Journal of Materials Chemistry*, **2007**, 17, 4598		15
248	Surface Induced Tilt Propagation in Thin Films of Semifluorinated Liquid Crystalline Side Chain Block Copolymers. *Macromolecules*, **2007**, 40, 81-89	5.5	42
247	Surface organization, light-driven surface changes, and stability of semifluorinated azobenzene polymers. *Langmuir*, **2007**, 23, 5110-9	4	53
246	Diazonaphthoquinone Molecular Glass Photoresists: Patterning without Chemical Amplification. *Chemistry of Materials*, **2007**, 19, 3780-3786	9.6	37
245	Arylonium Photoacid Generators Containing Environmentally Compatible Aryloxyperfluoroalkanesulfonate Groups. *Chemistry of Materials*, **2007**, 19, 1434-1444	9.6	32
244	Physical Vapor Deposition of Molecular Glass Photoresists: A New Route to Chemically Amplified Patterning. *Advanced Functional Materials*, **2007**, 17, 2336-2342	15.6	18

243	Creating Defined 3-D Defects Inside an Opaline Ormocer Matrix with Two-Photon Lithography. *Macromolecular Rapid Communications*, **2007**, 28, 922-926	4.8	9
242	Insight in the role of bovine serum albumin for promoting the in situ surface growth of polyhydroxybutyrate (PHB) on patterned surfaces via enzymatic surface-initiated polymerization. *Colloids and Surfaces B: Biointerfaces*, **2007**, 60, 68-79	6	12
241	Phenolic molecular glasses as resists for next-generation lithography **2007**, 6519, 1291		22
240	Control of Morphology Orientation in Lithographically Patternable Diblock Copolymers. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2007**, 20, 519-522	0.7	4
239	Patterned biofunctional poly(acrylic acid) brushes on silicon surfaces. *Biomacromolecules*, **2007**, 8, 3082-92	6.9	131
238	Positive- and Negative-Tone CVD Polyacrylic Electron-Beam Resists Developable by Supercritical CO2. *Chemical Vapor Deposition*, **2006**, 12, 259-262		17
237	Real-time analysis of enzymatic surface-initiated polymerization using surface plasmon resonance (SPR). *Macromolecular Bioscience*, **2006**, 6, 145-52	5.5	14
236	Control and Suppression of Surface Relief Gratings in Liquid-Crystalline Perfluoroalkyl Azobenzene Polymers. *Advanced Functional Materials*, **2006**, 16, 1577-1581	15.6	46
235	High-Resolution Patterning of Molecular Glasses Using Supercritical Carbon Dioxide. *Advanced Materials*, **2006**, 18, 442-446	24	41
234	Molecular glass resists for next generation lithography **2006**, 6153, 467		12
233	Absorbance measurement of polymers at extreme ultraviolet wavelength: Correlation between experimental and theoretical calculations. *Journal of Vacuum Science & Technology B*, **2006**, 24, 1822		23
232	Surfaces of fluorinated pyridinium block copolymers with enhanced antibacterial activity. *Langmuir*, **2006**, 22, 11255-66	4	114
231	Sub-50 nm feature sizes using positive tone molecular glass resists for EUV lithography. *Journal of Materials Chemistry*, **2006**, 16, 1470		66
230	Molecular Glass Resists for High-Resolution Patterning. *Chemistry of Materials*, **2006**, 18, 3404-3411	9.6	92
229	Comparison of the fouling release properties of hydrophobic fluorinated and hydrophilic PEGylated block copolymer surfaces: attachment strength of the diatom Navicula and the green alga Ulva. *Biomacromolecules*, **2006**, 7, 1449-62	6.9	238
228	Functionalized surface arrays for spatial targeting of immune cell signaling. *Journal of the American Chemical Society*, **2006**, 128, 5594-5	16.4	44
227	Anti-biofouling properties of comblike block copolymers with amphiphilic side chains. *Langmuir*, **2006**, 22, 5075-86	4	312
226	Supramolecular Microphase Separation in a Hydrogen-Bonded Liquid Crystalline Comb Copolymer in the Melt State. *Macromolecules*, **2006**, 39, 3114-3117	5.5	33

225	Adamantane based molecular glass resist for 193 nm lithography **2006**,		4
224	Supercritical CO 2 for high resolution photoresist development **2006**,		1
223	Molecular glass resists for EUV lithography **2006**,		5
222	Defining the Biology-Materials Interface using both 2D and 3D Lithography. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2006**, 19, 435-440	0.7	3
221	New PFOS Free Photoresist Systems for EUV Lithography. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2006**, 19, 515-520	0.7	6
220	Recent progress in high resolution lithography. *Polymers for Advanced Technologies*, **2006**, 17, 94-103	3.2	191
219	Block copolymer patterns and templates. *Materials Today*, **2006**, 9, 30-39	21.8	196
218	Dinitrophenyl ligand substrates and their application to immunosensors. *Biosensors and Bioelectronics*, **2006**, 22, 63-70	11.8	14
217	Molecular glass photoresists for advanced lithography. *Journal of Materials Chemistry*, **2006**, 16, 1693		68
216	Materials for future lithography (Invited Paper) **2005**, 5753, 1		15
215	Three-Dimensional Microfabrication by Two-Photon Lithography. *MRS Bulletin*, **2005**, 30, 976-982	3.2	39
214	Low Surface Energy Characteristics of Mesophase-Forming ABC and ACB Triblock Copolymers with Fluorinated B Blocks. *Molecular Crystals and Liquid Crystals*, **2005**, 441, 211-226	0.5	20
213	End-functionalization of poly(3-hydroxybutyrate)via genetic engineering for solid surface modification. *Chemical Communications*, **2005**, 1956-8	5.8	4
212	Oligo(ethylene glycol) containing polymer brushes as bioselective surfaces. *Langmuir*, **2005**, 21, 2495-504		125
211	Self-assembled monolayers and polymer brushes in biotechnology: current applications and future perspectives. *Biomacromolecules*, **2005**, 6, 2427-48	6.9	621
210	The convergence of top-down and bottom-up nanofabrication: formation of 3D structures **2005**, 5592, 12		
209	Inorganic polymer resists for EUVL **2005**, 5753, 732		5
208	Lithography Based on Molecular Glasses. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2005**, 18, 431-434	0.7	29

207	Silicon Containing Organic-Inorganic Hybrid Materials as EUV Photoresists. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2005**, 18, 481-487	0.7	5
206	Molecular templates for bio-specific recognition by low-energy electron beam lithography. *Nanobiotechnology*, **2005**, 1, 023-034		16
205	Functional Hydrogel Surfaces: Binding Kinesin-Based Molecular Motor Proteins to Selected Patterned Sites. *Advanced Functional Materials*, **2005**, 15, 1303-1309	15.6	26
204	Synthesis, Characterization and Lithography Performance of Photoacid Generator with Short Perfluoroalkyl Anion. *Polymer Bulletin*, **2005**, 55, 333-340	2.4	4
203	Directing self-assembly in macromolecular systems: Hydrogen bonding in ordered polymers. *Pure and Applied Chemistry*, **2004**, 76, 1337-1343	2.1	13
202	Towards all-dry lithography: Electron-beam patternable poly(glycidyl methacrylate) thin films from hot filament chemical vapor deposition. *Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena*, **2004**, 22, 2473		31
201	Patternable block copolymers with high transparency at 157 nm: Fluorocarbinol functionalized poly(isoprene-b-cyclohexane). *Polymer Bulletin*, **2004**, 52, 321-328	2.4	4
200	Managing polymer surface structure using surface active block copolymers in block copolymer mixtures. *Journal of Polymer Science, Part B: Polymer Physics*, **2004**, 42, 411-420	2.6	19
199	Fluorinated polymers: liquid crystalline properties and applications in lithography. *Chemical Record*, **2004**, 4, 315-30	6.6	49
198	Orientational Switching of Mesogens and Microdomains in Hydrogen-Bonded Side-Chain Liquid-Crystalline Block Copolymers Using AC Electric Fields. *Advanced Functional Materials*, **2004**, 14, 364-370	15.6	57
197	Additive-Driven Phase-Selective Chemistry in Block Copolymer Thin Films: The Convergence of Top□Down and Bottom□Up Approaches. *Advanced Materials*, **2004**, 16, 953-957	24	93
196	Swelling and dissolution rate measurements of polymer thin films in supercritical carbon dioxide. *Journal of Supercritical Fluids*, **2004**, 31, 323-328	4.2	17
195	Controlled degradation of epoxy networks: analysis of crosslink density and glass transition temperature changes in thermally reworkable thermosets. *Polymer*, **2004**, 45, 1939-1950	3.9	93
194	Heat capacity measurements of two-dimensional self-assembled hexadecanethiol monolayers on polycrystalline gold. *Applied Physics Letters*, **2004**, 84, 5198-5200	3.4	34
193	Photoprocessable Polymer Opals. *Chemistry of Materials*, **2004**, 16, 5286-5292	9.6	26
192	Spatially Controlled Fabrication of Nanoporous Block Copolymers. *Chemistry of Materials*, **2004**, 16, 3800-3808	9.6	95
191	Tribute to Professor Helmut Ringsdorf. *Macromolecules*, **2004**, 37, 8485-8486	5.5	1
190	Alignment of Self-Assembled Hierarchical Microstructure in Liquid Crystalline Diblock Copolymers Using High Magnetic Fields. *Macromolecules*, **2004**, 37, 9903-9908	5.5	117

189	Control of surface properties using fluorinated polymer brushes produced by surface-initiated controlled radical polymerization. *Langmuir*, **2004**, 20, 10498-506	4	78
188	Attogram detection using nanoelectromechanical oscillators. *Journal of Applied Physics*, **2004**, 95, 3694-3703	2.5	475
187	Two-Photon Three-Dimensional Microfabrication of Poly(Dimethylsiloxane) Elastomers. *Chemistry of Materials*, **2004**, 16, 5556-5558	9.6	87
186	Enzymatic surface-initiated polymerization: a novel approach for the in situ solid-phase synthesis of biocompatible polymer poly(3-hydroxybutyrate). *Biomacromolecules*, **2004**, 5, 889-94	6.9	35
185	Silicon backbone polymers as EUV resists **2004**,		5
184	Structural organisations in polystyrene-based semifluorinated block copolymers for low surface energy coatings. *Surface Coatings International Part B: Coatings Transactions*, **2004**, 87, 77-82		4
183	Synthesis and Phase Behavior of Side-Group Liquid Crystalline Polymers in Nematic Solvents. *Macromolecules*, **2004**, 37, 3569-3575	5.5	9
182	Novel resists with nontraditional compositions for EUV lithography **2004**,		8
181	Preparation and Two-Photon Lithography of a Sulfur Containing Resin with High Refractive Index. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2004**, 17, 115-118	0.7	14
180	Fluoropolymer resists for 157 nm lithography **2003**, 5039, 539		3
179	Novel silicon-containing polymers as photoresist materials for EUV lithography **2003**,		8
178	Malolactonate polymers and copolymers for biomedical applications. *Macromolecular Symposia*, **2003**, 197, 303-314	0.8	4
177	Surface patterning and biological evaluation of semi-interpenetrated poly(HEMA)/poly(alkyl malolactonate)s. *Macromolecular Symposia*, **2003**, 197, 369-380	0.8	8
176	Strategies for High Transparency Acrylate Resists for 157 nm Lithography. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2003**, 16, 573-580	0.7	4
175	Lithographic Patterning with Block Copolymers. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2003**, 16, 347-350	0.7	9
174	Chemically Amplified Positive Resists for Two-Photon Three-Dimensional Microfabrication. *Advanced Materials*, **2003**, 15, 517-521	24	62
173	An overview of supercritical CO2 applications in microelectronics processing. *Microelectronic Engineering*, **2003**, 65, 145-152	2.5	157
172	Design and application of high-sensitivity two-photon initiators for three-dimensional microfabrication. *Journal of Photochemistry and Photobiology A: Chemistry*, **2003**, 158, 163-170	4.7	98

171	Deintercalation of a chemically switchable polymer from a layered silicate nanocomposite. *Journal of Polymer Science, Part B: Polymer Physics*, **2003**, 41, 3151-3159	2.6	6
170	Rod□oil block copolymers: An iterative synthetic approach via living free-radical procedures. *Journal of Polymer Science Part A*, **2003**, 41, 3640-3656	2.5	44
169	Positive-Tone Photoresist Process for Supercritical Carbon Dioxide Development. *Chemistry of Materials*, **2003**, 15, 4893-4895	9.6	25
168	Methods for the topographical patterning and patterned surface modification of hydrogels based on hydroxyethyl methacrylate. *Biomacromolecules*, **2003**, 4, 1126-31	6.9	64
167	Structural Studies of Extension-Induced Mesophase Formation in Poly(diethylsiloxane) Elastomers:□ In Situ Synchrotron WAXS and SAXS. *Macromolecules*, **2003**, 36, 1975-1981	5.5	28
166	Liquid Crystalline Rod□oil Block Copolymers by Stable Free Radical Polymerization: Synthesis, Morphology, and Rheology. *Macromolecules*, **2003**, 36, 3357-3364	5.5	72
165	Coatings based on side-chain ether-linked poly(ethylene glycol) and fluorocarbon polymers for the control of marine biofouling. *Biofouling*, **2003**, 19 Suppl, 91-8	3.3	121
164	Synthesis and evaluation of novel organoelement resists for EUV lithography **2003**,		7
163	Fluorinated mesogen-jacketed liquid-crystalline polymers as surface-modifying agents: Design, synthesis and characterization. *Macromolecular Chemistry and Physics*, **2002**, 203, 1573-1583	2.6	60
162	Characterization of thermally reworkable thermosets: materials for environmentally friendly processing and reuse. *Polymer*, **2002**, 43, 131-139	3.9	124
161	Study of the interlayer expansion mechanism and thermal□echanical properties of surface-initiated epoxy nanocomposites. *Polymer*, **2002**, 43, 4895-4904	3.9	177
160	Dissolution rate measurements for resist processing in supercritical carbon dioxide **2002**, 4690, 425		2
159	New Strategies for High Resolution Photoresists.. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2002**, 15, 603-611	0.7	28
158	Organoelement resists for EUV lithography **2002**,		3
157	Fluorinated dissolution inhibitors for 157-nm lithography **2002**, 4690, 477		2
156	High-sensitivity two-photon photoacid generator for three-dimensional microfabrication **2002**, 4809, 170		1
155	Microfabrication of hydrogels for biomedical applications **2002**,		2
154	Highly transparent resist platforms for 157-nm microlithography: an update **2002**,		14

153	Semifluorinated Aromatic Side-Group Polystyrene-Based Block Copolymers:Bulk Structure and Surface Orientation Studies. *Macromolecules*, **2002**, 35, 8078-8087	5.5	105
152	Tailoring Transparency of Imageable Fluoropolymers at 157 nm by Incorporation of Hexafluoroisopropyl Alcohol to Photoresist Backbones. *Chemistry of Materials*, **2002**, 14, 1306-1313	9.6	25
151	An efficient two-photon-generated photoacid applied to positive-tone 3D microfabrication. *Science* , **2002**, 296, 1106-9	33.3	646
150	Self-assembly. Persistence pays off. *Science*, **2002**, 296, 859-61	33.3	14
149	Engineering low surface energy polymers through molecular design: synthetic routes to fluorinated polystyrene-based block copolymers. *Journal of Materials Chemistry*, **2002**, 12, 1684-1692		71
148	Lithographic Applications of Redox Probe Microscopy. *Langmuir*, **2001**, 17, 5932-5938	4	21
147	Rejuvenation of 248nm Resist Backbones for 157nm Lithography.. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2001**, 14, 613-620	0.7	15
146	Development of a bond contribution model for structure: property correlations in dry etch studies **2001**, 4345, 945		2
145	Fluorinated 2-Vinylcyclopropane Copolymers as Low Surface Energy Materials. *Macromolecular Symposia*, **2001**, 169, 303-312	0.8	1
144	E-Beam Patterning of Hot-Filament CVD Fluorocarbon Films Using Supercritical CO2 as a Developer. *Chemical Vapor Deposition*, **2001**, 7, 195		21
143	Patterning of Polymeric Hydrogels for Biomedical Applications. *Macromolecular Rapid Communications*, **2001**, 22, 1284	4.8	32
142	Defect-mediated creep of structured materials. *Europhysics Letters*, **2001**, 54, 269-274	1.6	20
141	High-pressure cell for simultaneous small-angle x-ray scattering and laser light scattering measurements. *Review of Scientific Instruments*, **2001**, 72, 2679-2685	1.7	12
140	Highly Reactive 2,5-Disubstituted Styrene-Based Monomer Polymerized via Stable Free Radical Polymerization:Effect of Substitution and Liquid Crystallinity on Polymerization. *Macromolecules*, **2001**, 34, 5120-5124	5.5	36
139	Synthesis, Characterization, and Redox Reactivity of Novel Quinone-Containing Polymer. *Chemistry of Materials*, **2001**, 13, 2928-2932	9.6	35
138	Periodic Surface Topology of Three-Arm Semifluorinated Alkane Monodendron Diblock Copolymers. *Langmuir*, **2001**, 17, 4342-4346	4	25
137	Design strategies for 157-nm single-layer photoresists: lithographic evaluation of a poly(-trifluoromethyl vinyl alcohol) copolymer **2000**,		14
136	Polyesters with semifluorinated side chains: A proposal for the solid-state structure. *Journal of Polymer Science, Part B: Polymer Physics*, **2000**, 38, 1617-1625	2.6	11

135	A solvent-free method for the synthesis of block copolymers with fluorinated pendant groups by a hydrosilylation reaction. *Journal of Polymer Science Part A*, **2000**, 38, 1179-1183	2.5	14
134	Photochromism of 4-cyanophenylazobenzene in liquid crystalline-coil AB diblock copolymers: the influence of microstructure. *Macromolecular Rapid Communications*, **2000**, 21, 1309-1312	4.8	33
133	Switching surface polarity: synthesis and characterization of a fluorinated block copolymer with surface-activetert-butoxycarbonyl groups. *Journal of Physical Organic Chemistry*, **2000**, 13, 787-795	2.1	13
132	Understanding and controlling the morphology of styrene□isoprene side-group liquid crystalline diblock copolymers. *Polymer*, **2000**, 41, 8897-8907	3.9	65
131	Microdeformation of a polydomain, smectic liquid crystalline thermoset. *Journal of Materials Science*, **2000**, 35, 2079-2086	4.3	29
130	Synchrotron Radiation for Probing the Electric Field Alignment of LC Macromolecules and Polymers. *International Journal of Polymeric Materials and Polymeric Biomaterials*, **2000**, 45, 451-501	3	3
129	Synchrotron x-ray study of the smectic layer directional instability. *Physical Review E*, **2000**, 61, 1593-8	2.4	11
128	Shape persistence of synthetic polymers. *Science*, **2000**, 288, 448-9	33.3	33
127	Temperature Dependence of Molecular Orientation on the Surfaces of Semifluorinated Polymer Thin Films. *Langmuir*, **2000**, 16, 1993-1997	4	76
126	Low-Surface-Energy Fluoromethacrylate Block Copolymers with Patternable Elements. *Chemistry of Materials*, **2000**, 12, 33-40	9.6	88
125	Selectively Thermally Cleavable Fluorinated Side Chain Block Copolymers:□Surface Chemistry and Surface Properties. *Macromolecules*, **2000**, 33, 1310-1320	5.5	47
124	Effect of Changing Molecular End Groups on Surface Properties: Synthesis and Characterization of Poly(styrene-b-semifluorinated isoprene) Block Copolymers with □F2H End Groups. *Macromolecules*, **2000**, 33, 8012-8019	5.5	49
123	Molecular Orientation of Single and Two-Armed Monodendron Semifluorinated Chains on □Soft□ and □Hard□Surfaces Studied Using NEXAFS. *Macromolecules*, **2000**, 33, 6068-6077	5.5	50
122	Surface Stability in Liquid-Crystalline Block Copolymers with Semifluorinated Monodendron Side Groups. *Macromolecules*, **2000**, 33, 6106-6119	5.5	103
121	Supercritical CO2 Processing for Submicron Imaging of Fluoropolymers. *Chemistry of Materials*, **2000**, 12, 41-48	9.6	81
120	The Orientation of Semifluorinated Alkanes Attached to Polymers at the Surface of Polymer Films. *Macromolecules*, **2000**, 33, 1882-1887	5.5	109
119	Fundamental Studies of Fluoropolymer Photoresists for 157 nm Lithography.. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **2000**, 13, 451-458	0.7	15
118	Photochromism of 4-cyanophenylazobenzene in liquid crystalline-coil AB diblock copolymers: the influence of microstructure **2000**, 21, 1309		1

117	Solid state crystalline and liquid crystalline structure of semifluorinated 1-bromoalkane compounds. *Liquid Crystals*, **1999**, 26, 637-648	2.3	34
116	Lithographic results of electron beam photoresists prepared by living free radical polymerization. *Polymer Bulletin*, **1999**, 43, 93-100	2.4	6
115	Effect of polymer architecture on self-diffusion of LC polymers. *Journal of Polymer Science, Part B: Polymer Physics*, **1999**, 37, 405-414	2.6	1
114	Liquid crystalline side chain-coil diblock copolymers by living free radical polymerization. *Macromolecular Rapid Communications*, **1999**, 20, 622-627	4.8	12
113	Mesogen-jacketed liquid crystalline polymers via stable free radical polymerization. *Macromolecular Chemistry and Physics*, **1999**, 200, 2338-2344	2.6	48
112	Development of reworkable underfills, materials, reliability and processing. *IEEE Transactions on Components and Packaging Technologies*, **1999**, 22, 163-167		5
111	Transverse Cylindrical Microdomain Orientation in an LC Diblock Copolymer under Oscillatory Shear. *Macromolecules*, **1999**, 32, 7703-7706	5.5	54
110	Block copolymers as additives: a route to enhanced resist performance **1999**,		3
109	Diffusion and Distribution of Photoacid Generators in thin Polymer Films. *Materials Research Society Symposia Proceedings*, **1999**, 584, 155		
108	Diffusion and Distribution Studies of Photoacid Generators. Ion Beam Analysis in Lithograpy.. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **1999**, 12, 457-467	0.7	18
107	Structure Development in Side Group Liquid Crystalline Diblock Copolymers **1999**, 9-28		1
106	Controlled-Order Thermosets for Electronic Packaging **1999**, 283-287		
105	Synthesis and Characterization of Thermally Degradable Polymer Networks. *Chemistry of Materials*, **1998**, 10, 3833-3838	9.6	96
104	Synthesis and Surface Energy Measurement of Semi-Fluorinated, Low-Energy Surfaces *Macromolecules*, **1998**, 31, 4272-4276	5.5	32
103	Smectic networks obtained from twin LC epoxy monomers mechanical deformation of the smectic networks. *Journal of Polymer Science, Part B: Polymer Physics*, **1998**, 36, 31-38	2.6	21
102	Flow-induced structure in a thermotropic liquid crystalline polymer as studied by SANS. *Journal of Polymer Science, Part B: Polymer Physics*, **1998**, 36, 3017-3023	2.6	8
101	Curvature driven relaxation of disclination loops in liquid crystals. *Polymer*, **1998**, 39, 4497-4503	3.9	7
100	Stress relaxation of a main-chain, smectic, polydomain liquid crystalline elastomer. *Polymer*, **1998**, 39, 3713-3718	3.9	83

99	Synthesis and mechanical properties of semi-flexible polymer networks. *Polymer Gels and Networks*, **1998**, 6, 291-300		3
98	Molecular Orientation and Dynamics in Ferroelectric Diblock Copolymers Monitored by FT-IR Spectroscopy. *Macromolecules*, **1998**, 31, 9008-9012	5.5	7
97	Deformation of a Polydomain, Liquid Crystalline Epoxy-Based Thermoset. *Macromolecules*, **1998**, 31, 4074-4088	5.5	146
96	Deformation of a Polydomain, Smectic Liquid Crystalline Elastomer. *Macromolecules*, **1998**, 31, 8531-8539	5.5	89
95	Microphase-Stabilized Ferroelectric Liquid Crystals (MSFLC):Bistable Switching of Ferroelectric Liquid CrystalCoil Diblock Copolymers. *Chemistry of Materials*, **1998**, 10, 1538-1545	9.6	48
94	Reworkable Epoxies: Thermosets with Thermally Cleavable Groups for Controlled Network Breakdown. *Chemistry of Materials*, **1998**, 10, 1475-1482	9.6	162
93	Copolymer approach to charge-dissipating electron-beam resists. *Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena*, **1998**, 16, 3701		4
92	Twin nematic phenylbenzoates in a.c. electric fields. *Liquid Crystals*, **1998**, 25, 199-206	2.3	2
91	Ferroelectric block copolymers. *Macromolecular Symposia*, **1997**, 117, 175-179	0.8	8
90	Order within order: Studies of semifluorinated block copolymers. *Macromolecular Symposia*, **1997**, 118, 701-706	0.8	2
89	Mixtures of Liquid-Crystalline and Amorphous Dicyanates: Unusual Curing Behavior and Mechanical Properties. *Chemistry of Materials*, **1997**, 9, 1588-1597	9.6	3
88	Orientation of Liquid Crystalline Epoxides under ac Electric Fields. *Macromolecules*, **1997**, 30, 4278-4287	5.5	63
87	Self-Organizing Materials with Low Surface Energy: The Synthesis and Solid-State Properties of Semifluorinated Side-Chain Ionenes. *Macromolecules*, **1997**, 30, 7560-7567	5.5	99
86	Effect of the Monomer Ratio on the Strengthening of Polymer Phase Boundaries by Random Copolymers. *Macromolecules*, **1997**, 30, 6727-6736	5.5	28
85	Multiple length scale self-organization in liquid crystalline block copolymers. *Macromolecular Symposia*, **1997**, 117, 141-152	0.8	6
84	Influence of a liquid crystalline block on the microdomain structure of block copolymers. *Macromolecular Symposia*, **1997**, 117, 241-256	0.8	29
83	Molecular Design, Synthesis, and Characterization of Liquid CrystalCoil Diblock Copolymers with Azobenzene Side Groups. *Macromolecules*, **1997**, 30, 2556-2567	5.5	209
82	Liquid Crystalline, Semifluorinated Side Group Block Copolymers with Stable Low Energy Surfaces: Synthesis, Liquid Crystalline Structure, and Critical Surface Tension. *Macromolecules*, **1997**, 30, 1906-1914	5.5	291

81	High Refractive Index Polymers for Optical Applications. *Journal of Macromolecular Science - Pure and Applied Chemistry*, **1997**, 34, 573-586	2.2	17
80	Amplification by optical composites. *Optics Letters*, **1997**, 22, 1247-9	3	69
79	Rigid rod and liquid crystalline thermosets. *Progress in Polymer Science*, **1997**, 22, 975-1000	29.6	100
78	Nanocomposite Materials for Optical Applications. *Chemistry of Materials*, **1997**, 9, 1302-1317	9.6	888
77	Competing Interactions and Levels of Ordering in Self-Organizing Polymeric Materials. *Science*, **1997**, 277, 1225-1232	33.3	643
76	Smectic rheology. *Rheologica Acta*, **1997**, 36, 498-504	2.3	50
75	Analysis of smectic structure formation in liquid crystalline thermosets. *Polymer*, **1997**, 38, 5857-5867	3.9	40
74	Polyelectrolyte–Surfactant Complexes in the Solid State: Facile building blocks for self-organizing materials. *Advanced Materials*, **1997**, 9, 17-31	24	233
73	Imaging polymers with supercritical carbon dioxide. *Advanced Materials*, **1997**, 9, 1039-1043	24	29
72	Block copolymers containing liquid crystalline segments. *Acta Polymerica*, **1997**, 48, 405-422		89
71	Liquid crystalline networks from 1,4-benzenedicarboxylic acid bis(4-cyanatomethylphenyl) ester. *Macromolecular Chemistry and Physics*, **1997**, 198, 2957-2970	2.6	9
70	Covalently Linked, Transparent Silica–Poly(imide) Hybrids. *Polymers for Advanced Technologies*, **1997**, 8, 289-296	3.2	31
69	Translational Diffusion in Polydisperse Polymer Samples Studied by Dynamic Imaging of Diffusion ESR. *The Journal of Physical Chemistry*, **1996**, 100, 15856-15866		13
68	Molecular Dynamics of a Liquid Crystalline Polymer Studied by Two-Dimensional Fourier Transform and CW ESR. *The Journal of Physical Chemistry*, **1996**, 100, 15873-15885		32
67	Structural Characterization of Biphenyl Ester-Based LC Molecules: Peculiarities of Cyclic Siloxane-Based Materials. *Macromolecules*, **1996**, 29, 8717-8725	5.5	7
66	Molecular Association in Nematic Phases of Cyclic Liquid Crystal Oligomers. *Macromolecules*, **1996**, 29, 8706-8716	5.5	9
65	Group-Transfer Polymerization of tert-Butyl Methacrylate and [3-(Methacryloxy)propyl]pentamethyldisiloxane: Synthesis and Characterization of Homopolymers and Random and Block Copolymers. *Chemistry of Materials*, **1996**, 8, 2272-2281	9.6	8
64	Lithographic Properties of Poly(tert-butyl methacrylate)-Based Block and Random Copolymer Resists Designed for 193 nm Wavelength Exposure Tools. *Chemistry of Materials*, **1996**, 8, 2282-2290	9.6	26

63	Surface Segregation Studies of Fluorine-Containing Diblock Copolymers *Macromolecules*, **1996**, 29, 1229-1234	5.5	217
62	Formation of Transparent Silica Polymer Hybrids Based on Siloxane-Containing Polyimides. *ACS Symposium Series*, **1996**, 392-402	0.4	1
61	Rotational Diffusion and Order Parameters of a Liquid Crystalline Polymer Studied by ESR: Molecular Weight Dependence. *The Journal of Physical Chemistry*, **1996**, 100, 15867-15872		15
60	Orientation-On-Demand Thin Films: Curing of Liquid Crystalline Networks in ac Electric Fields. *Science*, **1996**, 272, 252-255	33.3	60
59	The Processing of LC Thermosets in Orienting External Fields. *Materials Research Society Symposia Proceedings*, **1996**, 425, 149		2
58	Supercritical fluid processing: opportunities for new resist materials and processes **1996**,		2
57	Block and random copolymer resists designed for 193-nm lithography and environmentally friendly supercritical CO 2 development **1996**, 2724, 410		2
56	Block Copolymers as Lithographic Materials.. *Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]*, **1996**, 9, 1-11	0.7	5
55	Self-Assembled Smectic Phases in Rod-Coil Block Copolymers. *Science*, **1996**, 273, 343-6	33.3	385
54	Synthesis and curing of novel LC twin epoxy monomers for liquid crystal thermosets. *Journal of Polymer Science Part A*, **1996**, 34, 1291-1303	2.5	69
53	The curing of dicyanate ester liquid crystalline thermosets. *Angewandte Makromolekulare Chemie*, **1996**, 240, 59-66		1
52	Synthesis and curing of novel LC twin epoxy monomers for liquid crystal thermosets **1996**, 34, 1291		1
51	Nematic-smectic biphase of a main-chain liquid crystalline polyether. *Journal of Materials Science*, **1995**, 30, 2023-2028	4.3	2
50	Thermotropic liquid crystalline polymers with low thermal transitions. II. Low melting thermotropic liquid crystalline homo- and co-polyesters. *Journal of Polymer Science Part A*, **1995**, 33, 1913-1916	2.5	5
49	Block copolymers with low surface energy segments: siloxane- and perfluoroalkane-modified blocks. *Polymer*, **1995**, 36, 1321-1325	3.9	49
48	Dai et al. Reply. *Physical Review Letters*, **1995**, 74, 2837	7.4	7
47	The effect of electric and magnetic fields on the melt organization of a nematic cyclic siloxane liquid crystal. *Liquid Crystals*, **1995**, 18, 787-794	2.3	10
46	Zigzag Morphology of a Poly(styrene-b-hexyl isocyanate) Rod-Coil Block Copolymer. *Macromolecules*, **1995**, 28, 1688-1697	5.5	192

45	Silicon-Containing Block Copolymer Resist Materials. *ACS Symposium Series*, **1995**, 281-298	0.4	8
44	Novel ceramic particle synthesis for optical applications: Dispersion polymerized preceramic polymers as size templates for fine ceramic powders. *Advanced Materials*, **1995**, 7, 1009-1012	24	27
43	Probing the electric field alignment of a thermotropic liquid crystalline polymer by synchrotron radiation. *Liquid Crystals*, **1994**, 17, 179-190	2.3	17
42	Reinforcement of polymer interfaces with random copolymers. *Physical Review Letters*, **1994**, 73, 2472-2475	7.4	128
41	Crystallization of Precursors to Forsterite and Chromium-Doped Forsterite. *Journal of the American Ceramic Society*, **1994**, 77, 33-40	3.8	7
40	Synthesis and Lithographic Characterization of Block Copolymer Resists Consisting of Both Poly(styrene) Blocks and Hydrosiloxane-Modified Poly(diene) Blocks. *Chemistry of Materials*, **1994**, 6, 927-934	9.6	27
39	Viscoelastic properties of a model main-chain liquid crystalline polyether. *Journal of Rheology*, **1994** , 38, 1623-1638	4.1	44
38	Linear viscoelasticity of side chain liquid crystal polymer. *Liquid Crystals*, **1993**, 13, 233-245	2.3	51
37	The temperature dependence of nematic liquid crystalline polymer melt diffusion. *Liquid Crystals*, **1993**, 14, 1351-1358	2.3	7
36	Development of Poly(Phenylene)-Based Materials for Thin Film Applications: Optical Waveguides and Low Dielectric Materials. *Journal of Macromolecular Science - Pure and Applied Chemistry*, **1993**, 30, 877-897	2.2	9
35	Diffusion and melt viscosity of a main-chain liquid crystalline polyether. *Macromolecules*, **1993**, 26, 3764-3771	3.5	26
34	An investigation of the smectic-isotropic transition in a side-chain liquid crystal polymer by synchrotron radiation x-ray diffraction. *Journal of Polymer Science, Part B: Polymer Physics*, **1993**, 31, 773-777	2.6	10
33	Liquid crystalline and rigid-rod networks. *Progress in Polymer Science*, **1993**, 18, 899-945	29.6	137
32	Synthesis of Novel Fluorinated [sgrave]-Conjugated Silicon-Containing Polymers: Polysilynes and Polysilanes. *Journal of Macromolecular Science - Pure and Applied Chemistry*, **1992**, 29, 787-800	2.2	5
31	Rigid-rod thermosets based on 1,3,5-triazine-linked aromatic ester segments. *Macromolecules*, **1992**, 25, 2947-2954	5.5	71
30	Liquid crystalline epoxy thermosets based on dihydroxymethylstilbene: Synthesis and characterization. *Journal of Polymer Science Part A*, **1992**, 30, 1831-1843	2.5	96
29	The mechanical and magnetic alignment of liquid crystalline epoxy thermosets. *Journal of Polymer Science Part A*, **1992**, 30, 1845-1853	2.5	85
28	New liquid crystal polyethers and polyesters based on diphenylbutadiene mesogens. *Journal of Polymer Science Part A*, **1992**, 30, 2541-2547	2.5	3

27	Acid-catalyzed photoaromatization of poly(cyclohexadiene-1,2-diol) derivatives into polyphenylene. *Polymer Bulletin*, **1992**, 28, 33-40	2.4	8
26	Poly(methacrylate) Precursors to Forsterite. *Journal of the American Ceramic Society*, **1992**, 75, 1831-1838	3.8	22
25	Dynamic x-ray diffraction studies of liquid-crystalline polyesters. *Journal of Polymer Science, Part B: Polymer Physics*, **1990**, 28, 1047-1062	2.6	9
24	New thermotropic polyesters from distyrylbenzene bisphenols. *Journal of Polymer Science, Part C: Polymer Letters*, **1990**, 28, 331-339		6
23	Liquid crystal copolyethers with mixed mesogenic units and flexible spacers. *Polymer Bulletin*, **1990**, 23, 535-542	2.4	5
22	Dispersion copolymerization in non-aqueous media. *Makromolekulare Chemie Macromolecular Symposia*, **1990**, 35-36, 87-104		33
21	Studies of liquid-crystalline polymer phase transitions using synchrotron x-radiation. *Macromolecules*, **1989**, 22, 498-500	5.5	6
20	Polymer tacticity in simulated NMR spectra. *Journal of Chemical Education*, **1989**, 66, 645	2.4	3
19	Liquid crystalline polyesters by staged-addition polycondensation. *Polymer Bulletin*, **1988**, 20, 45	2.4	2
18	Synthesis and characterization of pyrene-labeled hydroxypropyl cellulose and its fluorescence in solution. *Macromolecules*, **1987**, 20, 38-44	5.5	69
17	Formation of large monodisperse copolymer particles by dispersion polymerization. *Macromolecules*, **1987**, 20, 268-273	5.5	160
16	The effect of temperature and initiator levels on the dispersion polymerization of polystyrene. *Journal of Polymer Science Part A*, **1987**, 25, 1395-1407	2.5	107
15	Coloured particles by dispersion polymerization. *European Polymer Journal*, **1987**, 23, 617-622	5.2	18
14	Partitioning of monomer during dispersion polymerisation. *Colloids and Surfaces*, **1986**, 21, 347-354		13
13	Thermotropic liquid crystalline polyesters containing naphthalenic mesogenic groups. *Polymer Bulletin*, **1986**, 15, 233	2.4	13
12	Monodispersed, micron-sized polystyrene particles by dispersion polymerization. *Journal of Polymer Science, Polymer Letters Edition*, **1985**, 23, 103-108		166
11	Particle size control in dispersion polymerization of polystyrene. *Canadian Journal of Chemistry*, **1985**, 63, 209-216	0.9	289
10	Liquid crystal polymers, 13. A smectic aromatic polyester with triad mesogenic groups and a polymethylene spacer in the main chain. *Die Makromolekulare Chemie Rapid Communications*, **1983**, 4, 49-55		32

9	Liquid-crystalline polymers. 12. Polyesters with either alternating or random orientation of mesogenic units. *Macromolecules*, **1983**, 16, 1034-1036	5.5	38
8	Liquid Crystal Polymers. V. Thermotropic Polyesters with Either Dyad or Triad Aromatic Ester Mesogenic Units and Flexible Polymethylene Spacers in the Main Chain. *Polymer Journal*, **1982**, 14, 9-17	2.7	98
7	Phase transitions in alkylene glycol terephthalate copolyesters containing mesogenic p-oxybenzoate units. *Polymer Bulletin*, **1981**, 5-5, 497	2.4	2
6	Thermotropic Liquid Crystalline Polyesters with Rigid or Flexible Spacer Groups. *British Polymer Journal*, **1980**, 12, 132-146		158
5	Phase-Selective Chemistry in Block Copolymer Systems1-66		1
4	Patternable Block Copolymers183-226		113
3	Block Copolymers Containing Liquid Crystalline Segments66-92		
2	Influence of spin casting solvent on the self-assembly of silicon-containing block copolymer thin films via high temperature thermal treatment. *Polymer International*,	3.3	1
1	Ionic Dopant-Induced Ordering Enhances the Thermoelectric Properties of a Polythiophene-Based Block Copolymer. *Advanced Functional Materials*,2106991	15.6	0